

The Development and the commercialization of the Mask Aligner for wafer  
Midas System will continue to grow along with the value creation for our customers.



www.midas-system.com

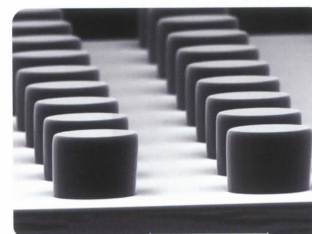
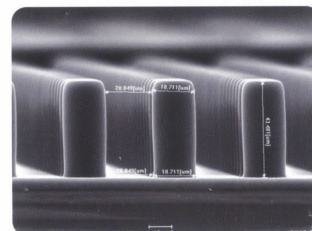
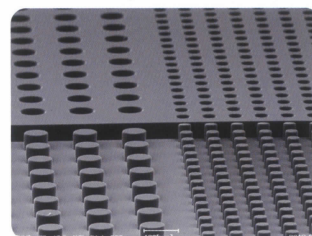
## MDA-60MS



The MDA-60MS offers a higher alignment accuracy and more flexible process of all applications. This is good for piece to 6inch process for research and reliable. This stabilized system will give you a reduction of experimental hours at all times.



▼ SEM Image



ITEM	SPECIFICATIONS
Substrate Size	Up to 6 inch (option 8 inch)
UV Lamp Power	1 kW (Option : 350W, 500W)
Resolution	0.8 $\mu$ m with 1 $\mu$ m thin PR @ Si wafer
Alignment Accuracy	0.5 $\mu$ m
Lamp Uniformity	$\leq 3\%$ (6")
Uniform Beam Size	9.25" $\times$ 9.25"
365nm Beam Intensity	$\leq 25\text{mW}/\text{cm}^2$
Exposure Time	0.1 ~ 999.9 sec
Process mode	Vacuum, Hard, Soft and Proximity
Option	BSA(CCD type), UV-NIL, UV intensity meter
Dimension	1,400 $\times$ 1,100 $\times$ 1,600 mm



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